

## **LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD**

### **ABSTRACT OF THE DISCLOSURE**

A programmable patterning structure for use with a lithographic  
5 projection apparatus according to one embodiment of the invention includes a  
plurality of reflective elements A, B, C, each reflective element having two  
distributed Bragg reflectors 51, 52. A separation D1 between the two  
distributed Bragg reflectors is adjustable between a first relation, at which  
destructive interference between reflections from the first and second  
10 distributed Bragg reflectors 51, 52 results in substantially zero reflectivity, and  
a second relation, in which constructive interference between reflections from  
the first and second distributed Bragg reflectors 51, 52 results in high  
reflectivity.